



PTO/SB/08A (10-01)
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U.S. Patent and Trademark Office: U.S. DEPARTMENT OF COMMERCE

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Substitute for form 1449A/PTO		Complete if Known	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)		Application Number	10/627,155
		Filing Date	7/24/03
		First Named Inventor	Patel
		Art Unit	Not Yet Assigned 2813
		Examiner Name	Not Yet Assigned
Sheet 1 of 6	Attorney Docket Number	P102-US	

U.S. PATENT DOCUMENTS					
Examiner Initials	Cite No. 1	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number - Kind Code ² (if known)			
SW		US- 3,511,727	05-12-1970	Hays, R.G.	
SW		US- 4,190,488	02-26-1980	Winters, H.F.	
SW		US- 4,310,380	12-12-1982	Fiamm et al.	
SW		US- 4,498,953	02-12-1985	Cook et al.	
SW		US- 6,051,503	04-18-2000	Bhardwai, J.K.	
SW		US- 6,436,229	08-20-2002	Tai et al.	
SW		US- 6,162,367	12-19-2000	Tai et al.	
SW		US- 6,290,864 B1	09-18-2001	Patel et al.	
SW		US- 6,355,181 B1	03-12-2002	McQuarrie, A.D.	
SW		US- 2001/0002663 A1	06-07-2001	Tai et al.	
SW		US- 5,439,553	08-08-1995	Grant et al.	
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SW		US- 2002/0196524 A1	12-26-2002	Huibers, et al.	
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SW		US- 5,726,480	03-10-1998	Pistor, K.S.	
SW		US- 2002/0185699 A1	12-12-2002	Reid	
SW		US- 2002/0121502 A1	09-15-2002	Patel, et al.	
SW		US- 5,835,256	11-10-1998	Huibers, A.	
SW		US- 2002/0047172 A1	04-25-2002	Reid	
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Examiner Initials ¹	Cite No. ¹	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ⁶
		Country Code ³ - Number ⁴ - Kind Code ⁵ (if known)				
SW		EP-0704884-A2	04-03-1996	Mehta, J.		
SW		EP-0822582-A2	02-04-1998	Bhardwaj, J.K.		
SW		EP-0822584-A2	04-04-1998	Bhardwaj, J.K.		
SW		WO-99/49506	09-30-1999	McQuarrie, A.D.		
SW		EP-0878824-A2	11-18-1998	McQuarrie et al.		
SW		EP-0878824-A3	01-19-2000	McQuarrie et al.		
SW		JP-1982/57098679-A	06-18-1982	Tsunetoshi, A.	Abstract Abstract Abstract	
SW		JP-1983/58130529-A	08-04-1983	Yoshihiro et al.		
SW		JP-1985/60057938-A	04-03-1985	Katsumi et al.		
SW		WO-98/32163	07-23-1998	Tai et al.		

Examiner Signature	<i>Stephen W. Smoot</i>	Date Considered	June 20, 2005
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Sheet	2	of	6
		Attorney Docket Number	P102-US

U.S. PATENT DOCUMENTS					
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		Number - Kind Code ² (if known)			
W.N.		US- 6,409,876 B1	06-25-2002	McQuarrie, et al.	
W.N.		US- 6,396,619 B1	05-28-2002	Huibers, et al.	
W.N.		US- 6,576,489 B2	06/10/03	Leung, et al.	
W.N.		US- 6,238,581	05-29-2001	Hawkins, et al.	
W.N.		US- 6,115,172	09-05-2000	Jeong	
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W.N.		US- 6,500,356 B2	12/31/02	Goto, et al.	
W.N.		US- 2003/0124848 A1	07/03/03	Chinn, et al.	
W.N.		US- 2003/0219986 A1	11/27/03	Rattner, et al.	
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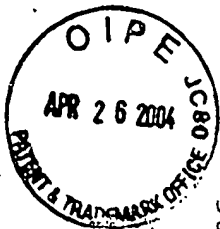
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W.N.		JP-1997/09251981-A	09-22-1997	Kazuaki et al.	Abstract	
W.N.		JP-1998/10313128-A	11-24-1998	Hanmin et al.	Abstract	
W.N.		JP-1998/10317169-A	12-02-1998	McQuarrie et al.	Abstract	
W.N.		JP-1986/61187238-A	08-20-1986	Nobuo et al.	Abstract	
W.N.		JP-1986/61270830-A	12-01-1986	Toru, T.	Abstract	
W.N.		JP-1987/62071217-A	04-01-1987	Toru et al.	Abstract	
W.N.		JP-1988/63155713-A	06-28-1988	Tadashi, F.	Abstract	
W.N.		JP-1986/61053732-A	03-17-1986	Arata et al.	Abstract	
W.N.		JP-1986/61134019-A	06-21-1986	Shinji et al.	Abstract	
W.N.		JP-1986/61181131-A	08-13-1986	Shinji et al.	Abstract	

Examiner Signature	Stephen W. Smoot	Date Considered	June 20, 2005
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		Filing Date	7/24/03		
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		Art Unit	Not Yet Assigned 2813		
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Sheet	3	of	6	Attorney Docket Number	P102-US

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		US-			
		US-			
		US-			
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Examiner Initials ⁵	Cite No. ¹	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	T ⁶
		Country Code ³ - Number ⁴ - Kind Code ² (if known)				
B.W.S.		JP-1989/01208834-A	08-22-1989	Nobuo et al.	Abstract	
		JP-1989/10217921-A 01217921-A	08-31-1989	Tsuneo et al.	Abstract	
		JP-1990/02250323-A	10-08-1990	Susumu et al.	Abstract	
		JP-1991/03012921-A	01-21-1991	Nobuo et al.	Abstract	
		JP-1992/04096222-A	03-27-1992	Atsuyuki, A.	Abstract	
		JP-1995/07029823-A	01-31-1995	Hiroshi, T.	Abstract	

Examiner Signature	Stephen W. Smoot	Date Considered	June 20, 2005
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		Application Number	10/627,155		
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (use as many sheets as necessary)		Filing Date	7/24/03		
		First Named Inventor	Patel		
		Group Art Unit	Not Yet Assigned 2813		
		Examiner Name	Not Yet Assigned		
Sheet	4	of	6	Attorney Docket Number	P102-US

OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS			
Examiner Initials	Cite No. 1	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published	T ²
S.W.S.		ALIEV et al., "Development of Si(100) Surface Roughness at the Initial Stage of Etching in F ₂ and XeF ₂ Gases Ellipsometric Study", Surface Science 442 (1999), pp. 206-214.	
S.W.S.		GLIDEMEISTER, J.M., "Xenon Difluoride Etching System" (Nov. 17, 1997).	
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S.W.S.		HECHT et al., "A Novel X-ray Photoelectron Spectroscopy Study of the Al/SiO ₂ Interface", J. Appl. Phys. Vol. 57 (June 15, 1985), pp. 5256-5261.	
S.W.S.		HOULE, F.A., "Dynamics of SiF ₄ Desorption During Etching of Silicon by XeF ₂ ", IBM Almaden Research Center (April 15, 1987), pp. 1866-1872.	
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S.W.S.		WINTERS, H.F., "Etch Products from the Reaction of XeF ₂ with SiO ₂ , SiO ₃ , Si ₃ N ₄ , SiC, and Si in the Presence of Ion Bombardment", J. Vac. Sci. Technol. B 1(4) (Oct/Dec 1983), pp. 927-931.	

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OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS			
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S.W.S.		Kurt Williams, Etch Rates for Micromachining Processing-Part II, 2003 IEEE, Pgs 761-778, Journal of Microelectromechanical Systems, Vol. 12, No. 6, December 2003.	
S.W.S.		WINTERS et al., "The Etching of Silicon with XeF ₂ Vapor", Appl. Phys. Letter, Vol. 34(1) (January 1, 1979), pp. 70-73.	
		XACTIX, Inc., Marketing Brochure (June 27, 1999).	
		Xenon Difluoride Isotropic Etch System: Seeing is Believing", Surface Technology Systems Ltd. brochure, Newport, UK (date unknown).	
S.W.S.		CHU et al., "Controlled Pulse-Etching with Xenon Difluoride", International Solid State Sensors and Actuators Conference (Transducers '97), Chicago, IL, Vol. 1 (June 16 - 19, 1997), pp. 665-668 (abstract only).	
S.W.S.		BASSOM et al., "Modeling and Optimizing XeF ₂ -enhanced FIB Milling of Silicon", 25th International Symposium for Testing and Failure Analysis, Santa Clara, CA (Nov. 14 - 18, 1999), pp. 255-261 (abstract only).	
S.W.S.		KOHLER et al., "Fabrication of Microlenses by Plasmaless Isotropic Etching Combined with Plastic Moulding", Sens. Actuators A, Phys. (Switzerland), Vol. A53, No. 1-3 (May 1996), pp. 361-363 (abstract only).	
S.W.S.		CHAN et al., "Gas Phase Pulse Etching of Silicon for MEMS with Xenon Difluoride", Engineering Solutions for the Next Millennium: 1999 IEEE Canadian Conference on Electrical and Computer Engineering, Edmonton, Alberta, Vol. 3 (May 9 - 12, 1999), pp. 1637-1642 (abstract only).	
S.W.S.		CHANG et al., "Gas-Phase Silicon Micromachining with ^{Xenon} Xenon Difluoride", Proceedings of the SPIE - The International Society for Optical Engineering, Vol. 2641 (1995), pp. 117-128 (abstract only).	

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8.2.2.8		SEBEL et al., "Reaction Layer Dynamics in Ion-Assisted Si/XeF ₂ Etching: Temperature Dependence", J. Vac. Sci. Technol. A, Vac. Surf. Films, Vol. 18, No. 6, (Nov. 2000), pp. 2759-2769 (abstract only).	
8.2.2.8		SEBEL et al., "Silicon Etch Rate Enhancement by Traces of Metal", J. Vac. Sci. Technol. A, Vac. Surf. Films, Vol. 17, No. 3, (May/June 1999), pp. 755-762 (abstract only).	
8.2.2.8		SUGANO et al., "Study on XeF ₂ Pulse Etching Using Wagon Wheel Pattern", Proceedings of the 1999 International Symposium on Micromechanics and Human Science: Towards the New Century, Nagoya, Japan (Nov. 23 - 26, 1999), pp. 163-167 (abstract only).	
		WANG et al., "Gas-Phase Silicon Etching with Bromine Trifluoride", International Solid State Sensors and Actuators Conference (Transducers '97), Chicago, IL, Vol. 2 (June 16 - 19, 1997), pp. 1505-1508 (abstract only).	
8.2.2.8		MUTHUKUMARAN et al., "Gas-Phase Xenon Difluoride Etching of Microsystems Fabricated Through the Mittel 1.5-μm CMOS Process", Can. J. Electr. Comput. Eng. (Canada), Vol. 25, No. 1 (Jan. 2000), pp. 35-41 (abstract only).	
8.2.2.8		TODA et al., "Thin Beam Bulk Micromachining Based on RIE and Xenon Difluoride Silicon Etching", International Solid State Sensors and Actuators Conference (Transducers '97), Chicago, IL, Vol. 1 (June 16 - 19, 1997), pp. 671-674.	
8.2.2.8		SEBEL et al., "Etching of Si Through a Thick Condensed XeF ₂ Layer", J. Vac. Sci. Technol. A, Vac. Surf. Films, Vol. 18, No. 5 (Sep/Oct 2000), pp. 2090-2097 (abstract only).	

Examiner Signature	Stephen W. Snoot	Date Considered	June 20, 2005
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			FILING DATE 7/24/03		GROUP Not Yet Assigned 2813		
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
<i>S.W.S.</i>	6,028,690	02/22/00	Carter, et al.				
FOREIGN PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
						<input type="checkbox"/>	<input type="checkbox"/>
						<input type="checkbox"/>	<input type="checkbox"/>
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
EXAMINER <i>Stephen W. Smart</i>	DATE CONSIDERED <i>June 20, 2005</i>						

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In re Application of: Patel, et al.

Art Unit: Not Yet Assigned

Serial No.: 10/627,155

Examiner: Not Yet Assigned

Filed: 7/24/03

For: **A MICROMIRROR ARRAY DEVICE WITH SMALL PITCH SIZE**

INFORMATION DISCLOSURE STATEMENT
PURSUANT TO 37 CFR 1.97(b)

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-145

Sir:

The attention of the Patent and Trademark Office is hereby directed to the following documents:

serial number 10,627,302 to Patel, et al, filed July 24, 2003;

serial number 10,627,303 to Patel, et al, filed July 24, 2003;

The attention of the Patent and Trademark Office is hereby also directed to the documents listed on the attached PTO Form 1449. Copies of the cited references are enclosed.

No fee or certification is required in connection with this Information Disclosure Statement, since it is being submitted prior to the last of (1) issuance of a first official action on the merits and (2) expiration of the three month period following filing of the above-captioned application.

The above information is presented so that the Patent and Trademark Office can determine any materiality thereof to the claimed invention. It is respectfully requested that the information be considered during the prosecution of this application and that the cited documents be listed on the front page of any patent issuing from this application.

Both
Considered
S.N.S.
6-18-05

[illegible]



SHEET 1 OF 1

INFORMATION DISCLOSURE CITATION PTO-1449			ATTY. DOCKET NO. P102-US		SERIAL NO. 10/627,155		
			APPLICANT Patel, et al				
			FILING DATE 7/24/03		GROUP Not Yet Assigned 2813		
U.S. PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE	
S.W.S.	2003/0160540	8/28/03	Miller, et al.	—	—		
S.W.S.	6,819,470	11/16/04	Meier, et al.	—	—		
S.W.S.	2003/0117688	6/26/03	Meier, et al.	—	—		
S.W.S.	2003/0117686	6/26/03	DiCarlo	—	—		
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	6,724,518	4/20/04	Meyer, et al.				
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S.W.S.	2004/0004753	1/8/04	Pan	—	—		
FOREIGN PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
S.W.S.	WO 2004/001487	12/13/03	PCT	—	—	<input type="checkbox"/>	<input type="checkbox"/>
S.W.S.	WO 2004/000720	12/13/03	PCT	—	—	<input type="checkbox"/>	<input type="checkbox"/>
S.W.S.	WO 2004/001717	12/13/03	PCT	—	—		
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
EXAMINER <u>Stephen W. Smoot</u>			DATE CONSIDERED <u>June 20, 2005</u>				

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.